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WHAT IS CLAIMED IS:

- A microarray comprising:
 a substrate comprising a primary aromatic amine diazotized surface; and
 at least one biomolecule covalently bound to said primary aromatic amine diazotized surface.
- 2. The microarray of claim 1, wherein said diazotized surface comprises a glass surface.
- 3. The microarray of claim 2, wherein said diazotized surface comprises a glass bead.
- 4. The microarray of claim 2, wherein said diazotized surface comprises a glass slide.
- 5. The microarray of claim 1, wherein said diazotized surface comprises a polymer surface.
- 6. The microarray of claim 5, wherein said diazotized surface comprises a plastic surface.
- 7. The microarray of claim 6, wherein said diazotized surface comprises polyethylene terephthalate.
- 8. The microarray of claim 1, wherein said diazotized surface comprises a silicon wafer.
- 9. The microarray of claim 1, wherein said diazotized surface comprises a ceramic surface.
- 10. The microarray of claim 1, wherein said diazotized surface comprises a metal oxide surface.
- 11. The microarray of claim 1, wherein said diazotized surface comprises a clay surface.
- 12. The microarray of claim 1, wherein said diazotized surface comprises a noble metal surface.
- 13. The microarray of claim 12, wherein said diazotized surface comprises a gold surface.
- 14. The microarray of claim 12, wherein said diazotized surface comprises a silver surface.
- 15. The microarray of claim 12, wherein said diazotized surface comprises a copper surface.
- 16. The microarray of claim 1, wherein said at least one biomolecule comprises a plurality of biomolecules.
- 17. The microarray of claim 16, wherein said plurality of biomolecules comprises at least two different biomolecules.
- 18. The microarray of claim 1, wherein said biomolecule comprises single-stranded DNA.

- 19. The microarray of claim 1, wherein said biomolecule comprises double-stranded DNA.
- 20. The microarray of claim 1, wherein said biomolecule comprises protein.
- 21. The microarray of claim 1, wherein said biomolecule comprises a ribozyme.
- 22. The microarray of claim 1, wherein said biomolecule comprises RNA.
- 23. The microarray of claim 1, wherein said biomolecule comprises an aptamer.
- 24. The microarray of claim 1, wherein said diazotized surface is part of a substrate having a thickness of approximately 1 mm.
- 25. The microarray of claim 1, wherein said diazotized surface comprises a siloxy diazotized surface.
- 26. The microarray of claim 25, wherein said siloxy diazotized surface comprises a glass surface.
- 27. The microarray of claim 26, wherein said siloxy diazotized surface comprises a glass bead.
- 28. The microarray of claim 26, wherein said diazotized surface comprises a glass slide.
- 29. The microarray of claim 25, wherein said siloxy diazotized surface comprises a polymer surface.
- 30. The microarray of claim 29, wherein said siloxy diazotized surface comprises a plastic surface.
- 31. The microarray of claim 30, wherein said siloxy diazotized surface comprises polyethylene terephthalate.
- 32. The microarray of claim 25, wherein said siloxy diazotized surface comprises a silicon wafer.
- 32. The microarray of claim 25, wherein said siloxy diazotized surface comprises a ceramic surface.
- 33. The microarray of claim 25, wherein said siloxy diazotized surface comprises a clay surface.
- 34. The microarray of claim 25, wherein said siloxy diazotized surface comprises a metal oxide surface.
- 35. The microarray of claim 25, wherein said siloxy diazotized surface comprises a siloxy amine diazonium group.
- 36. The microarray of claim 35, wherein said siloxy diazonium group comprises p-diazoniumphenyltrimethoxysilane salt.

- 37. The microarray of claim 25, wherein said at least one biomolecule comprises a plurality of biomolecules.
- 38. The microarray of claim 37, wherein said plurality of biomolecules comprises at least two different biomolecules.
- 39. The microarray of claim 25, wherein said biomolecule comprises single-stranded DNA.
- 40. The microarray of claim 25, wherein said biomolecule comprises double-stranded DNA.
- 41. The microarray of claim 25, wherein said biomolecule comprises protein.
- 42. The microarray of claim 25, wherein said biomolecule comprises a ribozyme.
- 43. The microarray of claim 25, wherein said biomolecule comprises RNA.
- 44. The microarray of claim 25, wherein said biomolecule comprises an aptamer.
- 45. The microarray of claim 25, wherein said siloxy diazotized surface is part of a substrate having a thickness of approximately 1 mm.
- 46. The microarray of claim 1, wherein said diazotized surface comprises a thiolate diazotized surface.
- 47. The microarray of claim 46, wherein said thiolate diazotized surface comprises a noble metal surface.
- 48. The microarray of claim 47, wherein said thiolate diazotized surface comprises a gold surface.
- 49. The microarray of claim 47, wherein said thiolate diazotized surface comprises a silver surface.
- 50. The microarray of claim 47, wherein said thiolate diazotized surface comprises a copper surface.
- 51. The microarray of claim 46, wherein said thiolate diazotized surface comprises a thiolate amine diazonium group.
- 52. The microarray of claim 51, wherein said thiolate amine diazonium group comprises p-diazoniumthiophene salt.
- 53. The microarray of claim 46, wherein said at least one biomolecule comprises a plurality of biomolecules.
- 54. The microarray of claim 53, wherein said plurality of biomolecules comprises at least two different biomolecules.

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- 55. The microarray of claim 46, wherein said biomolecule comprises single-stranded DNA.
- 56. The microarray of claim 46, wherein said biomolecule comprises double-stranded DNA.
- 57. The microarray of claim 46, wherein said biomolecule comprises protein.
- 58. The microarray of claim 46, wherein said biomolecule comprises a ribozyme.
- 59. The microarray of claim 46, wherein said biomolecule comprises RNA.
- 60. The microarray of claim 46, wherein said biomolecule comprises an aptamer.
- 61. The microarray of claim 46, wherein said thiolate diazotized surface is part of a substrate having a thickness of approximately 1 mm.
- 62. A siloxy diazotized surface.
- 63. The siloxy diazotized surface of claim 62, wherein said siloxy diazotized surface comprises a glass surface.
- 64. The siloxy diazotized surface of claim 63, wherein said siloxy diazotized surface comprises a glass bead.
- 65. The siloxy diazotized surface of claim 63, wherein said siloxy diazotized surface comprises a glass slide.
- 66. The siloxy diazotized surface of claim 62, wherein said siloxy diazotized surface comprises a polymer surface.
- 67. The siloxy diazotized surface of claim 66, wherein said siloxy diazotized surface comprises a plastic surface.
- 68. The siloxy diazotized surface of claim 67, wherein said siloxy diazotized surface comprises polyethylene terephthalate.
- 69. The siloxy diazotized surface of claim 62, wherein said siloxy diazotized surface comprises a silicon wafer.
- 70. The siloxy diazotized surface of claim 62, wherein said siloxy diazotized surface comprises a ceramic surface.

- 71. The siloxy diazotized surface of claim 62, wherein said siloxy diazotized surface comprises a ceramic surface.
- 72. The siloxy diazotized surface of claim 62, wherein said siloxy diazotized surface comprises a clay surface.
- 73. The siloxy diazotized surface of claim 62, wherein said siloxy diazotized surface comprises a siloxy amine diazonium group.
- 74. The siloxy diazotized surface of claim 73, wherein said siloxy diazonium group comprises p-diazoniumphenyltrimethoxysilane salt.
- 75. The siloxy diazotized surface of claim 62, wherein said siloxy diazotized surface is part of a substrate having a thickness of approximately 1 mm.
- 76. A method for forming a microarray comprising: treating an oxidized surface with a siloxy amine to form a siloxy amine treated surface; treating said siloxy amine treated surface with a diazotizing agent to form a siloxy diazotized surface; and

contacting said siloxy diazotized surface with at least one biomolecule to form a microarray in which said at least one biomolecule is covalently bound to said siloxy diazotized surface.

- 77. The method of claim 76, wherein said siloxy amine comprises a primary aromatic amine.
- 78. The method of claim 77, wherein said siloxy amine comprises p-aminophenyl trimethoxysilane (ATMS).
- 79. The method of claim 76, wherein said siloxy amine treated surface is formed by treating said oxidized surface with a siloxy amine comprising primary aromatic amine.
- 80. The method of claim 79, wherein said siloxy amine comprises p-aminophenyl trimethoxysilane (ATMS).
- 81. The method of claim 76, wherein said biomolecule contains a powerful electron-releasing group.
- 82. The method of claim 76, wherein said diazotizing agent comprises NaNO₂ and HCl.
- 83. The method of claim 76, wherein said siloxy diazotized surface is formed from said siloxy amine treated surface by exposing said siloxy amine treated surface to 5.2 mM NaNO₂ and 0.26 M HCl at 0-5 degrees centigrade for 30 minutes.

- 84. The method of claim 76, wherein said siloxy diazotized surface is formed from said siloxy amine treated surface by exposing said siloxy amine treated surface to 5.2 mM NaNO₂ and 0.26 M HCl at 0-5 degrees centigrade for 10-30 minutes.
- 85. The method of claim 76, wherein said siloxy diazotized surface is formed from said siloxy amine treated surface by exposing said siloxy amine treated surface to 5.2 mM NaNO₂ and 0.26 M HCl at 5-15 degrees centigrade for 30 minutes.
- 86. The method of claim 76, wherein said siloxy diazotized surface is formed from said siloxy amine treated surface by exposing said siloxy amine treated surface to 5.2 mM NaNO₂ and 0.26 M HCl at 5-15 degrees centigrade for 10-30 minutes.
- 87. The method of claim 76, wherein said siloxy diazotized surface is formed from said siloxy amine treated surface by exposing said siloxy amine treated surface to 5.2 mM NaNO₂ and 0.26 M HCl at 15-25 degrees centigrade for 30 minutes.
- 88. The method of claim 76, wherein said siloxy diazotized surface is formed from said siloxy amine treated surface by exposing said siloxy amine treated surface to 5.2 mM NaNO₂ and 0.26 M HCl at 15-25 degrees centigrade for 10-30 minutes.
- 89. The method of claim 76, wherein said siloxy diazotized surface is formed from said siloxy amine treated surface by exposing said siloxy amine treated surface to 5.2 mM NaNO₂ and 0.26 M HCl at room temperature for 30 minutes.
- 90. The method of claim 76, wherein said siloxy diazotized surface is formed from said siloxy amine treated surface by exposing said siloxy amine treated surface to 5.2 mM NaNO₂ and 0.26 M HCl at room temperature for 10-30 minutes.
- 91. The method of claim 76, further comprising treating a substrate surface with an oxidizing agent to form an oxidized surface.
- 92. The method of claim 91, wherein said substrate surface comprises a polymer surface.
- 93. The method of claim 92, wherein said substrate surface comprises a plastic surface.
- 94. The method of claim 93, wherein said substrate surface comprises polyethylene terephthalate.
- 95. The method of claim 76, wherein said siloxy diazotized surface comprises a glass surface.
- 96. The method of claim 95, wherein said siloxy diazotized surface comprises a glass bead.

- 97. The method of claim 95, wherein said siloxy diazotized surface comprises a glass slide.
- 98. The method of claim 76, wherein said siloxy diazotized surface comprises a polymer surface.
- 99. The method of claim 98, wherein said siloxy diazotized surface comprises a plastic surface.
- 100. The method of claim 99, wherein said siloxy diazotized surface comprises polyethylene terephthalate.
- 101. The method of claim 76, wherein said siloxy diazotized surface comprises a silicon wafer.
- 102. The method of claim 76, wherein said siloxy diazotized surface comprises a ceramic surface.
- 103. The method of claim 76, wherein said siloxy diazotized surface comprises a ceramic surface.
- 104. The method of claim 76, wherein said siloxy diazotized surface comprises a clay surface.
- 105. The method of claim 76, wherein said siloxy diazotized surface comprises a siloxy amine diazonium group.
- 106. The method of claim 105, wherein said siloxy amine diazonium group comprises p-diazoniumphenyltrimethoxysilane salt.
- 107. The method of claim 76, wherein said at least one biomolecule comprises a plurality of biomolecules.
- 108. The method of claim 107, wherein said plurality of biomolecules comprises at least two different biomolecules.
- 109. The method of claim 76, wherein said biomolecule comprises single-stranded DNA.
- 110. The method of claim 76, wherein said biomolecule comprises double-stranded DNA.
- 111. The method of claim 76, wherein said biomolecule comprises protein.
- 112. The method of claim 76, wherein said biomolecule comprises a ribozyme.
- 113. The method of claim 76, wherein said biomolecule comprises RNA.
- 114. The method of claim 76, wherein said biomolecule comprises an aptamer.

- 115. The method of claim 76, wherein said siloxy diazotized surface is part of a substrate having a thickness of approximately 1 mm.
- 116. A method for forming a siloxy diazotized surface comprising: treating an oxidized surface with a siloxy amine to form a siloxy amine treated surface; and treating said siloxy amine treated surface with a diazotizing agent to form a siloxy diazotized surface.
- 117. The method of claim 116, wherein said siloxy amine comprises a primary aromatic amine.
- 118. The method of claim 117, wherein said siloxy amine comprises p-aminophenyl trimethoxysilane (ATMS).
- 119. The method of claim 116, wherein said siloxy amine treated surface is formed by treating said oxidized surface with a siloxy amine comprising a primary aromatic amine.
- 120. The method of claim 119, wherein said siloxy amine comprises p-aminophenyl trimethoxysilane (ATMS).
- 121. The method of claim 116, wherein said diazotizing agent comprises NaNO₂ and HCl.
- 122. The method of claim 116, wherein said siloxy diazotized surface is formed from said siloxy amine treated surface by exposing said siloxy amine treated surface to 5.2 mM NaNO₂ and 0.26 M HCl at 0-5 degrees centigrade for 30 minutes.
- 123. The method of claim 116, wherein said siloxy diazotized surface is formed from said siloxy amine treated surface by exposing said siloxy amine treated surface to 5.2 mM NaNO₂ and 0.26 M HCl at 0-5 degrees centigrade for 10-30 minutes.
- 124. The method of claim 116, wherein said siloxy diazotized surface is formed from said siloxy amine treated surface by exposing said siloxy amine treated surface to 5.2 mM NaNO₂ and 0.26 M HCl at 5-15 degrees centigrade for 30 minutes.
- 125. The method of claim 116, wherein said siloxy diazotized surface is formed from said siloxy amine treated surface by exposing said siloxy amine treated surface to 5.2 mM NaNO₂ and 0.26 M HCl at 5-15 degrees centigrade for 10-30 minutes.
- 126. The method of claim 116, wherein said siloxy diazotized surface is formed from said siloxy amine treated surface by exposing said siloxy amine treated surface to 5.2 mM NaNO_2 and 0.26 M HCl at 15-25 degrees centigrade for 30 minutes.

- 127. The method of claim 116, wherein said siloxy diazotized surface is formed from said siloxy amine treated surface by exposing said siloxy amine treated surface to 5.2 mM NaNO₂ and 0.26 M HCl at 15-25 degrees centigrade for 10-30 minutes.
- 128. The method of claim 116, wherein said siloxy diazotized surface is formed from said siloxy amine treated surface by exposing said siloxy amine treated surface to 5.2 mM NaNO₂ and 0.26 M HCl at room temperature for 30 minutes.
- 129. The method of claim 116, wherein said siloxy diazotized surface is formed from said siloxy amine treated surface by exposing said siloxy amine treated surface to 5.2 mM NaNO₂ and 0.26 M HCl at room temperature for 10-30 minutes.
- 130. The method of claim 116, further comprising treating a substrate surface with an oxidizing agent to form an oxidized surface.
- 131. The method of claim 130, wherein said substrate surface comprises a polymer surface.
- 132. The method of claim 131, wherein said substrate surface comprises a plastic surface.
- 133. The method of claim 132, wherein said substrate surface comprises polyethylene terephthalate.
- 134. The method of claim 116, wherein said siloxy diazotized surface comprises a glass surface.
- 135. The method of claim 134, wherein said siloxy diazotized surface comprises a glass bead.
- 136. The method of claim 134, wherein said siloxy diazotized surface comprises a glass slide.
- 137. The method of claim 116, wherein said siloxy diazotized surface comprises a polymer surface.
- 138. The method of claim 137, wherein said siloxy diazotized surface comprises a plastic surface.
- 139. The method of claim 138, wherein said siloxy diazotized surface comprises polyethylene terephthalate.
- 140. The method of claim 116, wherein said siloxy diazotized surface comprises a silicon wafer.
- 141. The method of claim 116, wherein said siloxy diazotized surface comprises a ceramic surface.
- 142. The method of claim 116, wherein said siloxy diazotized surface comprises a metal oxide surface.
- 143. The method of claim 116, wherein said siloxy diazotized surface comprises a clay surface.

- 144. The method of claim 116, wherein said siloxy diazotized surface comprises a siloxy amine diazonium group.
- 145. The method of claim 144, wherein said siloxy diazonium group comprises p-diazoniumphenyltrimethoxysilane salt.
- 146. A method for using a microarray comprising the steps of:

contacting said microarray with a plurality of first free biomolecules to hybridize at least a portion of said plurality of first free biomolecules to bound biomolecules of said microarray; and

removing said first free biomolecules from said microarray without removing said bound biomolecules from said microarray.

- 147. The method of claim 146, further comprising the step of contacting said microarray with a plurality of second free biomolecules to hybridize at least a portion of said second free biomolecules to said bound biomolecules of said microarray.
- 148. The method of claim 146, further comprising the step of repeating step contained in claim 147.
- 149. The method of 146, wherein said microarray comprises:a substrate comprising a siloxy diazotized surface; andsaid bound molecules covalently bound to said siloxy diazotized glass surface.
- 150. The method of claim 149, wherein said bound biomolecule comprises a plurality of biomolecules.
- 151. The method of claim 150, wherein said plurality of biomolecules comprises at least two different biomolecules.
- 152. The method of claim 149, wherein said bound biomolecule comprises single-stranded DNA.
- 153. The method of claim 149, wherein said bound biomolecule comprises double-stranded DNA.
- 154. The method of claim 149, wherein said bound biomolecule comprises protein.
- 155. The method of claim 149, wherein said bound biomolecule comprises a ribozyme.
- 156. The method of claim 149, wherein said bound biomolecule comprises RNA.
- 157. The method of claim 149, wherein said bound biomolecule comprises an aptamer.

- 158. The method of claim 146, wherein said microarray comprises:a substrate comprising a thiolate diazotized surface; andsaid bound molecules covalently bound to said thiolate diazotized noble metal surface.
- 159. The method of claim 158, wherein said bound biomolecule comprises a plurality of biomolecules.
- 160. The method of claim 159, wherein said plurality of biomolecules comprises at least two different biomolecules.
- 161. The method of claim 158, wherein said bound biomolecule comprises single- stranded DNA.
- 162. The method of claim 158, wherein said biomolecule comprises double-stranded DNA.
- 163. The method of claim 158, wherein said biomolecule comprises protein.
- 164. The method of claim 158, wherein said biomolecule comprises a ribozyme.
- 165. The method of claim 158, wherein said bound biomolecule comprises RNA.
- 166. The method of claim 158, wherein said bound biomolecule comprises an aptamer.
- 167. A thiolate diazotized surface.
- 168. The thiolate diazotized surface of claim 167, wherein said thiolate diazotized surface comprises a noble metal surface.
- 169. The thiolate diazotized surface of claim 168, wherein said thiolate diazotized surface comprises a gold surface.
- 170. The thiolate diazotized surface of claim 168, wherein said thiolate diazotized surface comprises a silver surface.
- 171. The thiolate diazotized surface of claim 168, wherein said thiolate diazotized surface comprises a copper surface.
- 172. The thiolate diazotized surface of claim 167, wherein said thiolate diazotized surface comprises a thiolate amine diazonium group.
- 173. The thiolate diazotized surface of claim 172, wherein said thiolate amine diazonium group comprises p-diazoniumthiophene salt.

- 174. The thiolate diazotized surface of claim 167, wherein said diazotized surface is part of a substrate having a thickness of approximately 1 mm.
- 175. A method for forming a microarray comprising:
 treating a noble metal surface with a thiolate amine to form a thiolate amine treated surface;
 treating said thiolate amine treated surface with a diazotizing agent to form a thiolate diazotized surface;
 and

contacting said thiolate diazotized surface with at least one biomolecule to form a microarray in which said at least one biomolecule is covalently bound to said thiolate diazotized surface.

- 176. The method of claim 175, wherein said thiolate amine comprises a primary aromatic amine.
- 177. The method of claim 176, wherein said thiolate amine comprises 4-aminothiophene.
- 178. The method of claim 175, wherein said thiolate amine treated surface is formed by treating said noble metal surface with a thiolate amine comprising primary aromatic amine.
- 179. The method of claim 178, wherein said thiolate amine comprises 4-aminothiophene.
- 180. The method of claim 175, wherein said biomolecule contains a powerful electron-releasing group.
- 181. The method of claim 175, wherein said diazotizing agent comprises NaNO₂ and HCl.
- 182. The method of claim 175, wherein said thiolate diazotized surface is formed from said thiolate amine treated surface by exposing said thiolate amine treated surface to 5.2 mM NaNO₂ and 0.26 M HCl at 0-5 degrees centigrade for 30 minutes.
- 183. The method of claim 175, wherein said thiolate diazotized surface comprises a noble metal surface.
- 184. The method of claim 183, wherein said thiolate diazotized surface comprises a gold metal surface.
- 185. The method of claim 183, wherein said thiolate diazotized surface comprises a silver metal surface.
- 186. The method of claim 183, wherein said thiolate diazotized surface comprises a copper metal surface.
- 187. The method of claim 175, wherein said thiolate diazotized surface comprises a thiolate amine diazonium group.

- 188. The method of claim 187, wherein said thiolate amine diazonium group comprises p-diazoniumthiophene salt.
- 189. The method of claim 175, wherein said at least one biomolecule comprises a plurality of biomolecules.
- 190. The method of claim 189, wherein said plurality of biomolecules comprises at least two different biomolecules.
- 191. The method of claim 175, wherein said biomolecule comprises single- stranded DNA.
- 192. The method of claim 175, wherein said biomolecule comprises double-stranded DNA.
- 193. The method of claim 175, wherein said biomolecule comprises protein.
- 194. The method of claim 175, wherein said biomolecule comprises a ribozyme.
- 195. The method of claim 175, wherein said biomolecule comprises RNA.
- 196. The method of claim 175, wherein said biomolecule comprises an aptamer.
- 197. The method of claim 175, wherein said thiolate diazotized surface is part of a substrate having a thickness of approximately 1 mm.
- 198. A method for forming a thiolate diazotized surface comprising:
 treating a noble metal surface with a thiolate amine to form a thiolate amine treated surface; and
 treating said thiolate amine treated surface with a diazotizing agent to form a thiolate diazotized surface.
- 199. The method of claim 198, wherein said thiolate amine comprises a primary aromatic amine.
- 200. The method of claim 199, wherein said thiolate amine comprises 4-aminothiophene.
- 201. The method of claim 198, wherein said thiolate amine treated surface is formed by treating said noble metal surface with a thiolate amine comprising a primary aromatic amine.
- 202. The method of claim 201, wherein said thiolate amine comprises 4-aminothiophene.
- 203. The method of claim 198, wherein said diazotizing agent comprises NaNO₂ and HCl.

- 204. The method of claim 198, wherein said thiolate diazotized surface is formed from said thiolate amine treated surface by exposing said thiolate amine treated surface to 5.2 mM NaNO₂ and 0.26 M HCl at 0-5 degrees centigrade for 30 minutes.
- 205. The method of claim 198, wherein said thiolate diazotized surface comprises a noble metal surface.
- 206. The method of claim 205, wherein said thiolate diazotized surface comprises a gold surface.
- 207. The method of claim 205, wherein said thiolate diazotized surface comprises a silver surface.
- 208. The method of claim 205, wherein said thiolate diazotized surface comprises a copper surface.
- 209. The method of claim 205, wherein said thiolate diazotized surface comprises a thiolate amine diazonium group.
- 210. The method of claim 209, wherein said thiolate amine diazonium group comprises p-diazoniumthiophene salt.
- 211. A kit, comprising:a siloxy amine treated surface; anda diazotizing agent.
- 212. The kit of claim 211, further comprising at least one biomolecule.
- 213. The kit of claim 212, wherein said biomolecule is DNA.
- 214. The kit of claim 212, wherein said biomolecule is protein.
- 215. The kit of claim 212, wherein said biomolecule is RNA.
- 216. The kit of claim 211, wherein said surface has been stabilized.